IN THE CLAIMS

1. A curable resin composition comprising:

a copolymer (a) having a molecular structure in which a constitutional unit including an acidic functional group and a constitutional unit including a photocurable functional group are linked at least;

a photopolymerization initiator (b) having a tertiary amine structure; and

a photocurable compound (c) having at least one acidic functional group and at least three photocurable functional groups.

- 2. The curable resin composition according to claim 1, wherein the constitutional unit having the photocurable functional group of the copolymer (a) includes an ethylenically unsaturated bond as the photocurable functional group.
- 3. The curable resin composition according to claim 1 [[or 2]], wherein the copolymer (a) includes a constitutional unit represented by a following formula (1) and/or a constitutional unit represented by a following formula (2), as the constitutional unit having the photocurable unit:

Formula (1)

wherein R1 is a hydrogen atom or an alkyl group having 1 to 5 carbon atoms, and R2 is a hydrogen or a methyl group;

Formula (2)

wherein R1 is the same as defined above, R3 is an alkylene group having 2 to 4 carbon atoms, R4 is an alkylene group, and R5 is a hydrogen atom or a methyl group.

- 4. The curable resin composition according to any one of claims 1 [[to 3]], wherein the copolymer (a) has a molecular weight of 3,000 to 1,000,000.
- 5. The curable resin composition according to any one of claims 1 [[to 4]], further comprising a photocurable compound (d) having at least two photocurable functional groups with the proviso that the photocurable compound (d) is other than the photocurable compound (c).
- 6. The curable resin composition according to claim 5, wherein a weight ratio $((a) / \{(c) + (d)\})$ of the copolymer (a) to a total of the photocurable compound (c) and the photocurable compound (d) is up to 1.5, on the basis of solid content.
- 7. The curable resin composition according to any one of claims 1 [[to 6]], wherein the photopolymerization initiator (b) having the tertiary amine structure is contained at least 10% by weight, on the basis of solid content.
- 8. The curable resin composition according to any one of claims 1 [[to 7]], wherein the curable resin composition is used for fabricating a liquid crystal panel substrate.
 - A liquid crystal panel substrate comprising:
 a transparent substrate; and

a color layer disposed on the transparent substrate,

the liquid crystal panel substrate optionally comprising:

a protective film for covering the color layer; and/or

a spacer disposed in a non-display region on the substrate, characterized in that wherein

at least one of the protective film and the spacer is formed by curing the curable resin composition according to any one of claims 1 [[to 7]].

- 10. A liquid crystal panel comprising:
 - a display side substrate;
- a liquid crystal driving side substrate opposite to the display side substrate; and
- a liquid crystal filled and sealed between these two substrates, characterized in that wherein

at least one of the display side substrate and the liquid crystal driving side substrate is the liquid crystal panel substrate according to claim 9.

11. The curable resin composition according to claim 1, eharacterized in that wherein the photocurable compound (c) is an acidic group containing monomer (c3) represented by a following formula (11):

Formula (11)

$$R = \frac{(CH_2)_m}{(CH_2)_m} = \frac{(CH_2)_m}{(CH_2)_m} = O - X$$

$$(CH_2)_m = R$$

$$R: CH_2 = CH - C - O - CH_2 = C - C - O - CH_2$$

$$O = O - CH_2 = C - C - O - CH_2$$

$$X: -C = \frac{(CH_2)_m}{O} = C - O - C - O - CH_2$$

$$O = O - C - O - CH_2$$

wherein each of m and n is an integer equal to 1 or more than 1, independently.

- 12. The curable resin composition according to claim 11, capable of forming a convex pattern having a lower area S1 and an upper area S2 satisfying a relationship $S2 \le S1$, in processes including: forming a coating film and subjecting the coating film sequentially to a selective exposure and an alkali developing treatment.
- 13. The curable resin composition according to claim 11 [[or 12]], further comprising a photocurable compound (d) having at least two photocurable functional groups with the proviso that the photocurable compound (d) is other than the photocurable compound (c).
- 14. The curable resin composition according to any one of claims 11 [[to 13]], further comprising at least one kind of colorant (e), wherein a weight ratio ((e) / (c3)) of the colorant (e)acidic group containing monomer (c3) to the acidic group containing monomer (c3) colorant (e)-satisfies a relationship 0.3<((c) / (c3))<0.6.

- 15. A color filter comprising:
 - a transparent substrate; and
 - a color layer disposed on the transparent substrate,
 - the color filter optionally comprising:
 - a protective film for covering the color layer; and/or
- a spacer disposed in a non-display region on the transparent substrate,

wherein

- at least one of the color layer, the protective film and the spacer is formed by curing the photosensitive curable resin composition according to any one of claims 11 [[to 14]].
- 16. A liquid crystal panel substrate having a plurality of spacers disposed in a non-display region on a substrate, wherein the spacers are formed by curing the photosensitive curable resin composition according to any one of claims 11 [[to 14]].
 - 17. A liquid crystal panel comprising:
 - a display side substrate;
- a liquid crystal driving side substrate opposite to the display side substrate; and
 - a liquid crystal filled and sealed between these two substrates, wherein the display side substrate is the color filter according to claim 15.
 - 18. A liquid crystal panel comprising:
 - a display side substrate;
- a liquid crystal driving side substrate opposite to the display side substrate; and
 - a liquid crystal filled and sealed between these two substrates, wherein

the liquid crystal driving side substrate is the liquid crystal panel substrate according to claim 16.

19. The curable resin composition according to claim 1, for a use of forming a photosensitive pattern, characterized in that wherein

the copolymer (a) is an imide group containing copolymer (a1) containing a constitutional unit including a cyclic imide group represented by a following formula (19), as the constitutional unit including the photocurable functional group, and

the copolymer (a) is used for forming the photosensitive pattern:

Formula (19)

wherein each of R8 and R9 is an alkyl group having 4 or less carbon atoms independently, or one 0 of R8 and R9 is a hydrogen atom and the other is an alkyl group having 4 or less carbon atoms, or both R8 and R9 together form a carbon ring.

- 20. The curable resin composition for a use of forming a photosensitive pattern according to claim 19, wherein the imide group containing copolymer (a1) further contains a constitutional unit including another photocurable functional group other than the cyclic imide group.
- 21. The curable resin composition for a use of forming a photosensitive pattern according to claim 19 [[or 20]], wherein the constitutional unit of the imide group containing copolymer (al) contains an ethylenically unsaturated bond as a photocurable functional group other than the cyclic imide group.

22. The curable resin composition for a use of forming a photosensitive pattern according to any one of claims 19 [[to 21]], wherein the imide group containing copolymer (a1) contains a constitutional unit represented by a following formula (21) as the constitutional unit including the cyclic imide group and a constitutional unit represented by a following formula (3) as the constitutional unit including the acidic functional group:

Formula (21)

wherein R6 is a hydrogen <u>atom</u> or an alkyl group having 1 to 5 carbon atoms, R7 is an alkylene having 1 to 6 carbon atoms, R8 and R9 are the same as defined above;

Formula (3)

wherein R1 is a hydrogen <u>atom</u> or an alkyl group having 1 to 5 carbon atoms.

- 23. The curable resin composition for a use of forming a photosensitive pattern according to any one of claims 19 [[to 22]], wherein the imide group containing copolymer (a1) contains an alcoholic hydroxy group in its molecule.
- 24. The curable resin composition for a use of forming a photosensitive pattern according to any one of claims 19 [[to 23]], characterized in that wherein an

elastic deformation modulus [(elastic deformation amount / total deformation amount) X 100] against a compressive load of 2.0 GPa exhibits at least 60% at a room temperature after curing.

- 25. The curable resin composition for a use of forming a photosensitive pattern according to any one of claims 19 [[to 24]], further comprising: a photocurable compound (d) having at least two photocurable functional groups with the proviso that the photocurable compound (d) is other than the photocurable compound (c).
- 26. The curable resin composition for a use of forming a photosensitive pattern according to claim 25, characterized in that wherein the photocurable compound (d) (other than the compound (c)) contains at least three ethylenically unsaturated bonds as the photocurable functional group, and contains an alcoholic hydroxy group.
- 27. The curable resin composition for a use of forming a photosensitive pattern according to any one of claims 19 [[to 26]], wherein a solid content weight ratio ((a1) / (c)) of the imide group containing copolymer (a1) photocurable compound (c) to the photocurable compound (c) imide group containing copolymer [[(a1)]] in a case that the curable resin composition includes no photocurable compound (d) with the proviso that the photocurable compound (d) is other than the photocurable compound (c), or a solid content weight ratio ((a1) / {(c) + (d) }) of the imide group containing copolymer (a1)a total of the photocurable compound (e) and the photocurable compound (d) to a total of the photocurable compound (c) and the photocurable compound (d) the imide group containing copolymer (a1) in a case that the curable resin composition includes the photocurable compound (d), is 0.7 or less.
- 28. The curable resin composition for a use of forming a photosensitive pattern according to any one of claims 19 [[to 27]], wherein the photopolymerization

initiator (b) having the tertiary amine structure is contained at 0.05 to 5% by weight, on the basis of solid content.

- 29. The curable resin composition for a use of forming a photosensitive pattern according to any one of claims 19 [[to 28]], wherein the curable resin composition is used for fabricating a liquid crystal panel substrate.
 - 30. A liquid crystal panel substrata comprising:
 - a transparent substrate; and
 - a color layer disposed on the transparent substrate,
 - the liquid crystal panel substrate further comprising:
 - a protective film for covering the color layer; and/or
- a spacer disposed in a non-display region on the substrate, characterized in that wherein

at least one of the protective film and the spacer is formed by curing the curable resin composition according to any one of claims 19 [[to 29]].

- 31. The liquid crystal panel substrate according to claim 30, wherein the spacer has at least 60% of an elastic deformation modulus [(elastic deformation amount / total deformation amount) x 100] against a compressive load of 2.0 GPa at a room temperature.
 - 32. A liquid crystal panel comprising:
 - a display side substrate;
- a liquid crystal driving side substrate opposite to the display side substrate; and
- a liquid crystal filled and sealed between these two substrates, characterized in that wherein

at least one of the display side substrate and the liquid crystal driving side substrate is the liquid crystal panel substrate according to claim 30 [[or 31]].

- 33. The curable resin composition according to claim 1, characterized in that wherein the composition further comprises a colorant (e) and is used for forming a colorant pattern.
- 34. The curable resin composition for forming the colorant pattern according to claim 33, further comprising a photocurable compound (d) (other than the compound (c)) having at least two photocurable functional groups.
- 35. The curable resin composition for forming the colorant pattern according to claim 33 [[or 34]], containing the photocurable compound (c) of 3 to 30% by weight, on the basis of solid content.
- 36. The curable resin composition for forming the colorant pattern according to any one of claims 33 [[to 35]], wherein the photopolymerization initiator (b) having the tertiary amine structure is contained at least 5% by weight, on the basis of solid content.
- 37. The curable resin composition for forming the colorant pattern according to any one of claims 33 [[to 36]], wherein the copolymer (a) has a molecular weight of 3,000 to 1,000,000.
- 38. The curable resin composition for forming the colorant pattern according to any one of claims 33 [[to 37]], wherein the curable resin composition is used for forming a colorant pattern for a color filter.
 - 39. A color filter comprising:
 a transparent substrate; and
 a pixel disposed on the transparent substrate,
 the color filter optionally comprising:

a black matrix layer,

characterized in that wherein

the pixel and/or the black matrix layer are formed by curing the curable resin composition according to any one of claims 33 [[to 38]].

- 40. A liquid crystal panel comprising:
 - a display side substrate;
- a liquid crystal driving side substrate opposite to the display side substrate; and
- a liquid crystal filled and sealed between these two substrates,

characterized in that wherein

the display side substrate is the color filter according to claim 39.